Title (en)

Lithographic apparatus and device manufacturing method

Title (de)

Lithographischer Apparat und Verfahren zur Herstellung einer Vorrichtung

Title (fr)

Appareil lithographique et méthode de fabrication d'un dispositif

Publication

EP 1482372 B1 20141008 (EN)

Application

EP 04253057 A 20040525

Priority

- EP 04253057 A 20040525
- EP 03253420 A 20030530

Abstract (en)

[origin: EP1482372A1] The apparatus has a support structure supporting a patterning unit that patterns the projection beam according to a desired pattern. A projection system (PL) projects the patterned beam onto a target portion of the substrate. A liquid supply system fills the space between a final unit of the projection system and the substrate with an anti-reflective topcoat solution with a pH of less than seven. An independent claim is also included for a device manufacturing method.

IPC 8 full level

G03F 7/20 (2006.01)

CPC (source: EP)

G03F 7/70341 (2013.01); **G03F 7/70866** (2013.01); **G03F 7/70958** (2013.01)

Cited by

CN102262361A; EP1821338A4; CN106716255A; EP2073062A1; EP1791026A1; CN101055427A; US7903232B2; EP2267536A1; EP2267537A1; EP1528433A3; US8817227B2; WO2016020121A1; US10261422B2; US10534270B2; US7773195B2; US8456611B2; US8836912B2; US8953141B2; US9291914B2; WO2016096508A1; US10551748B2; US10859919B2; US8035799B2; US8913224B2; US10248034B2; US10527955B2; US8859188B2; US9164391B2; US9454088B2; US9772565B2; US10712675B2

Designated contracting state (EPC)

DE FR GB IT NL

DOCDB simple family (publication)

EP 1482372 A1 20041201; **EP 1482372 B1 20141008**

DOCDB simple family (application)

EP 04253057 A 20040525